

12-6-03

FULL FILE PROJECTIONS: ONLINE **COMPLETE**
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 PROJECTED ITERATIONS: 1 TO 80
 PROJECTED ANSWERS: 1 TO 80

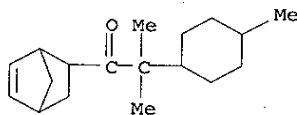
L4 1 SEA SSS SAM L2 AND L1

=> d

L4 ANSWER 1 OF 1 REGISTRY COPYRIGHT 2003 ACS on STN
 RN 474510-67-3 REGISTRY
 CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 3-
 hydroxytricyclo[3.3.1.1^{3,7}]dec-1-yl ester, polymer with
 1-bicyclo[2.2.1]hept-5-en-2-yl-2-methyl-2-(4-methylcyclohexyl)-1-
 propanone, 5-ethoxy-3a,4,5,6,7,7a-hexahydro-4,7-methano-1H-indene and
 2,5-furandione (9CI) (CA INDEX NAME)
 MF (C18 H28 O . C18 H24 O3 . C12 H18 O . C4 H2 O3)x
 CI PMS
 PCT Polyether, Polyvinyl
 SR CA
 LC STN Files: CA, CAPLUS

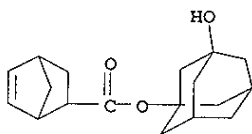
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CRN 474510-66-2
 CMF C18 H28 O



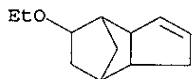
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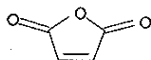
CM 3

CRN 53018-26-1
 CMF C12 H18 O



CM 4

CRN 108-31-6
 CMF C4 H2 O3



1 REFERENCES IN FILE CA (1907 TO DATE)
 1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

=> FIL HCAPLUS, CAPLUS, USPATFULL
 COST IN U.S. DOLLARS

SINCE FILE ENTRY TOTAL SESSION

FULL ESTIMATED COST

2.08

2.29

FILE 'HCAPLUS' ENTERED AT 15:29:53 ON 05 DEC 2003
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FILE 'USPATFULL' ENTERED AT 15:29:53 ON 05 DEC 2003
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

=> s 14

L5 2 L4

=> d 15 1-2 ibib hitstr

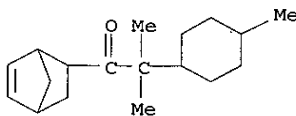
L5 ANSWER 1 OF 2 HCAPLUS COPYRIGHT 2003 ACS on STN
ACCESSION NUMBER: 2002:848220 HCAPLUS
DOCUMENT NUMBER: 137:360306
TITLE: Radiation-sensitive positively working photosensitive composition
INVENTOR(S): Kodama, Kunihiro; Sato, Kenichiro
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 92 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 4
PATENT INFORMATION:

| PATENT NO. | KIND | DATE | APPLICATION NO. | DATE |
|------------------------|------|----------|-----------------|------------|
| JP 2002323758 | A2 | 20021108 | JP 2001-157367 | 20010525 |
| US 2003017415 | A1 | 20030123 | US 2002-79414 | 20020222 |
| PRIORITY APPLN. INFO.: | | | | |
| | | | JP 2001-48783 | A 20010223 |
| | | | JP 2001-48602 | A 20010223 |
| | | | JP 2001-48784 | A 20010223 |
| | | | JP 2001-48880 | A 20010223 |
| | | | JP 2001-157366 | A 20010525 |
| | | | JP 2001-157367 | A 20010525 |

IT 474510-67-3P
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(radiation-sensitive pos. working photosensitive compn. for high resolu. and storage stability)
RN 474510-67-3 HCAPLUS
CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 3-hydroxytricyclo[3.3.1.1^{3,7}]dec-1-yl ester, polymer with 1-bicyclo[2.2.1]hept-5-en-2-yl-2-methyl-2-(4-methylcyclohexyl)-1-propanone, 5-ethoxy-3a,4,5,6,7,7a-hexahydro-4,7-methano-1H-indene and 2,5-furandione (9CI) (CA INDEX NAME)

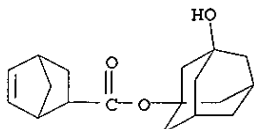
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CRN 474510-66-2
CMF C18 H28 O



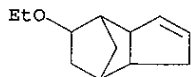
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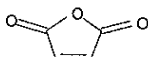
CM 3

CRN 53018-26-1
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CM 4

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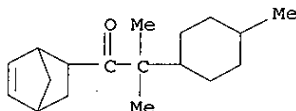
L5 ANSWER 2 OF 2 CAPLUS COPYRIGHT 2003 ACS on STN
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DOCUMENT NUMBER: 137:360306
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INVENTOR(S): Kodama, Kunihiko; Sato, Kenichiro
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| US 2003017415 | A1 | 20030123 | US 2002-79414 | 20020222 |
| PRIORITY APPLN. INFO.: | | | | |
| | | | JP 2001-48783 | A 20010223 |
| | | | JP 2001-48602 | A 20010223 |
| | | | JP 2001-48784 | A 20010223 |
| | | | JP 2001-48880 | A 20010223 |
| | | | JP 2001-157366 | A 20010525 |
| | | | JP 2001-157367 | A 20010525 |

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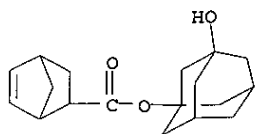
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CMF C18 H28 O



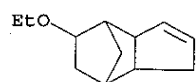
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CRN 331866-92-3
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CRN 53018-26-1
CMF C12 H18 O



CM 4

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